

Application No. 10/594,537
Paper Dated: July 30, 2008
In Reply to USPTO Correspondence of March 31, 2008
Attorney Docket No. 5038-062725

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : 10/594,537 Confirmation No. 3363
Applicants : HO-SEONG NAM et al.
Filed : September 27, 2006
Title : CHEMICAL MECHANICAL POLISHING SLURRY
COMPOSITION FOR SHALLOW TRENCH
ISOLATION PROCESS OF SEMICONDUCTOR
Group Art Unit : 1792
Examiner : Patricia Ann George
Customer No. : 28289

Mail Stop Amendment
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450


AMENDMENT

Sir:

In response to the Office Action dated March 31, 2008, Applicants submit the following amendments and remarks.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.

I hereby certify that this correspondence is being electronically submitted to the United States Patent and Trademark Office on July 30, 2008	
07/30/2008	
Date	Signature
Sharon L. Haney	
Typed Name of Person Signing Certificate	